

International Workshop
«Atomic Layer Deposition: Russia, 2015»

September 21-23, 2015, Moscow Institute of Physics and technology (state university),
Dolgoprudny, Russia

Dear colleagues,

we are pleased to announce the **International Workshop «Atomic Layer Deposition: Russia, 2015»**

Atomic Layer Deposition (ALD) is a thin film coating technique, which has gradually manifested itself as a powerful tool to fabricate ultrathin, highly uniform and conformal material layers for many applications including semiconductor integrated circuits industry, sensors, III-V devices, micro/nanoelectromechanical systems (MEMS/NEMS) manufacturing, optics, optoelectronics, solar cell production, biocompatible coatings for medical devices, etc. Although Russian (Soviet) scientists had played significant role in developing the scientific principles of the method in 1960s, until recently the potential of ALD technique for various applications was not fully exploited in Russia. However, over the last decade the interest to this cross-disciplinary field of material science has attracted renewed attention.

The idea of the Workshop “*Atomic Layer Deposition: Russia, 2015*” is to consolidate the rapidly growing Russian ALD community, and to bring closer Russian researchers to the leading international experts in the field.

Reputable scientists of the leading research centers will take part in the International Workshop "ALD Russia 2015":

Anatoly A. Malygin (*St. Petersburg Technological University, Russia*),
Gregory N. Parsons (*North Carolina State University, USA*),
Steven M. George (*University of Colorado at Boulder, USA*),
Vladimir Gritsenko (*Rzhanov Institute of Semiconductor Physics SB RAS, Russia*),
Cheol Seong Hwang (*Seoul National University, Korea*),
Giovanna Scarel (*James Madison University, USA*),
Evgeni Gornev (*SRIME, Russia*),
Annelies Delabie (*IMEC, Belgium*),
Sabina Spiga (*CNR-IMM-MDM, Italy*),
Igor Igumenov (*A V Nikolaev Institute of Inorganic Chemistry, Russia*),
Rikka Puuronen (*VTT, Finland*),
Robert M. Wallace (*University of Texas at Dallas, USA*),
Erwin Von Kessel (*Eindhoven University of Technology, Netherlands*),
Ingo Dirnstorfer (*Namlab, Germany*),
Vladislav Vasiliev (*Novosibirsk state technical university and SibIS LLC, Russia*),
Sean Barry (*Carleton University, Canada*)



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